FIG. 1

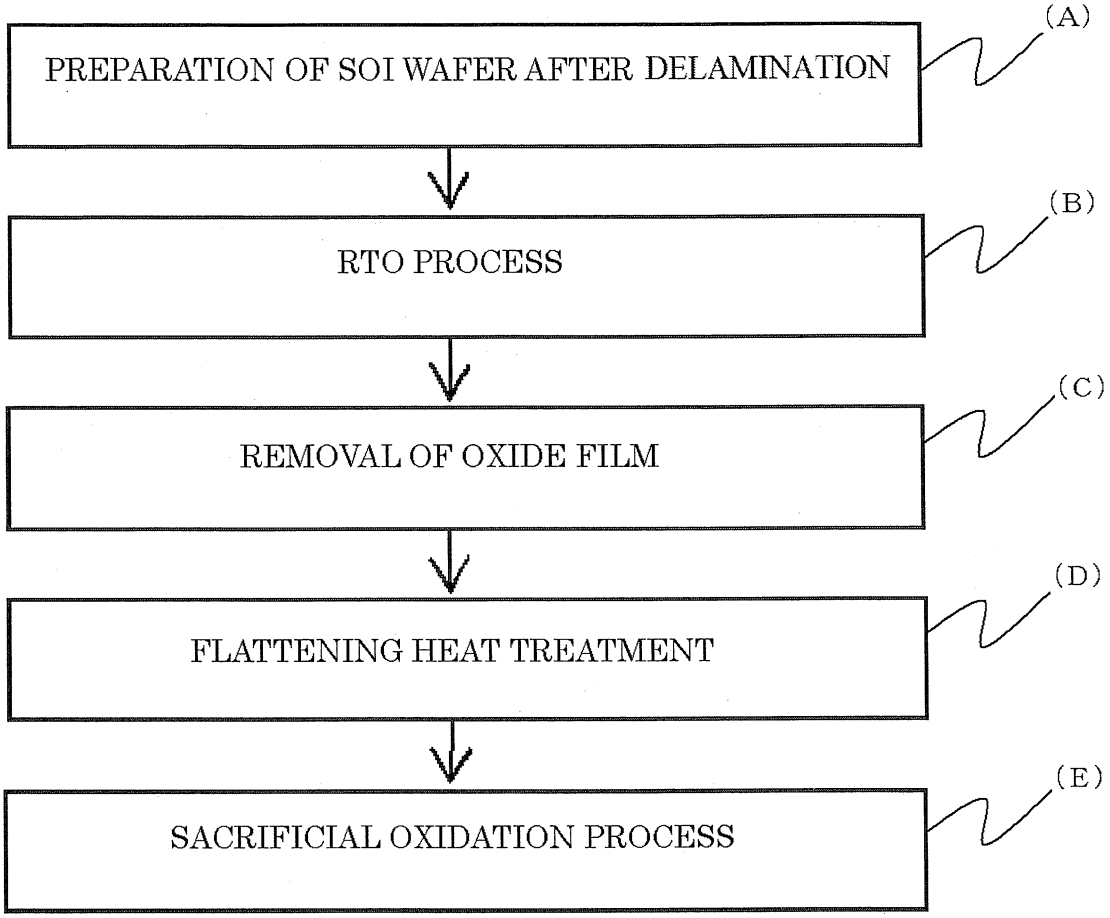

PREPARATION OF SOI WAFER AFTER DELAMINATION
(A)
RTO PROCESS
(B)
REMOVAL OF OXIDE FILM
(C)
FLATTENING HEAT TREATMENT
(D)
SACRIFICIAL OXIDATION PROCESS
(E)

FIG. 2

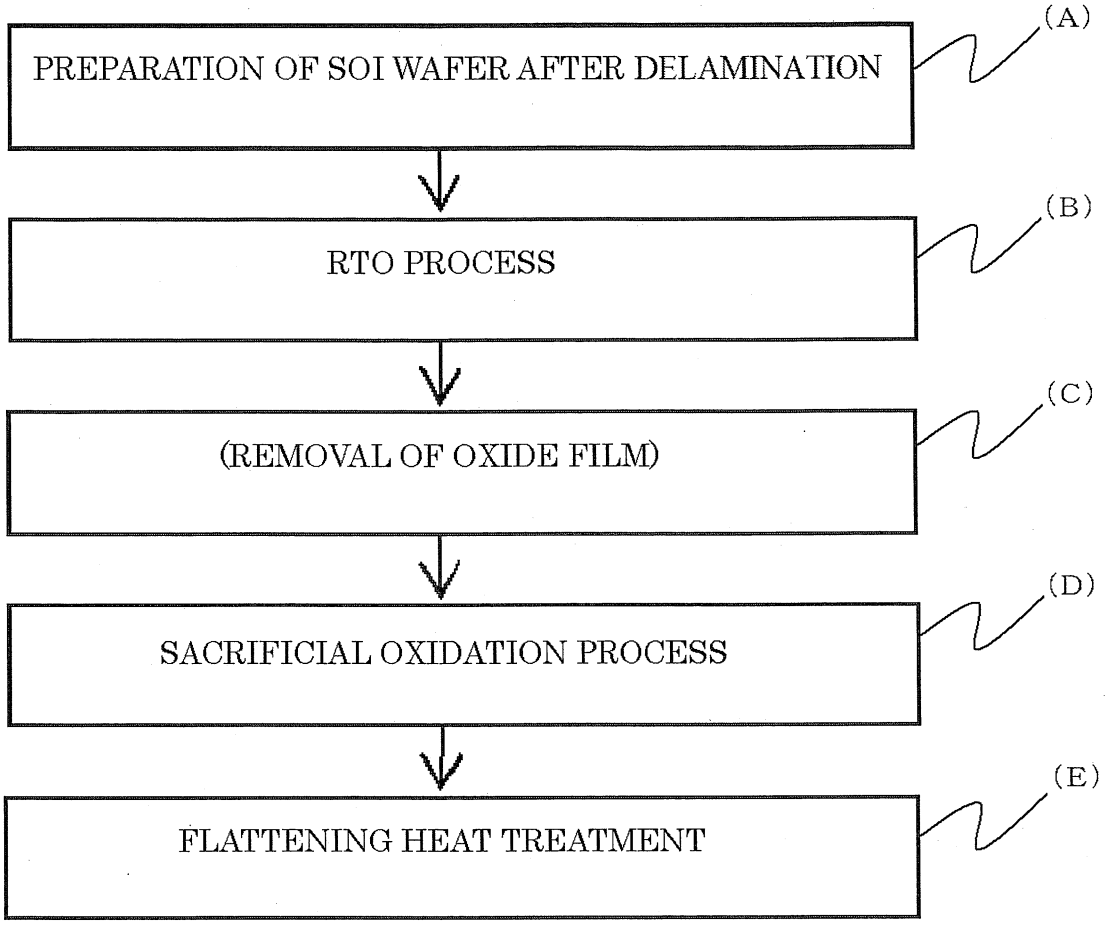

PREPARATION OF SOI WAFER AFTER DELAMINATION
(A)
RTO PROCESS
(B)
(REMOVAL OF OXIDE FILM)
(C)
SACRIFICIAL OXIDATION PROCESS
(D)
FLATTENING HEAT TREATMENT
(E)

FIG. 3

